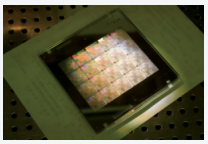
Photolitography patterning

APPLICATIONS

Semiconductor 	1. Electronic circuit formation 2. Dielectric layer formation
Display 	1. Transistor and color filter 2. RGB layer formation (Color Resist)

THEORY, KNOWLEDGE, & MODELS

Theory	**Patterning**	Photolithography
Process	**Coating**	1. Spin coating 2. Softbake
	UV exposure	1. Mask alignment 2. UV Exposure
	Develop	1. Develop
Materials		1. General Photoresist 2. Photo sensitive Polyimide

CAPABILITIES

Core Equipment at ADL Ewha site
1. Spin coating on Substrate
2. Mask Alignment and UV Exposure
3. Develop

Core Competitiveness at ADL Ewha

1. **Photo Sensitive Material Formulation Testing**

2. Coating and Patternability Evaluation

3. Analysis and Reliability Testing

Evaluation Data Library

Commercialized Products	**AZ series, JSR Series**
Customized Products	

Current Project Introduction

No	Project Title
1	Photo Sensitive PI development at Ewha ADL Team
2	
3	